

Abstract Submitted  
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**CVD synthesis of graphene** TAO JIANG, JOEL THERRIEN, U. Massachusetts-Lowell — We will report on the use of Chemical Vapor Deposition (CVD) to grow sheets of graphene on substrates suitable for the semiconductor industry. Growth starts with the deposition of seed crystals of graphene on the substrate. CVD growth is found to result in growth at the edges of the seeds, rather than on the surfaces. The result is increases in the size of the seed crystal without additional layers of graphene forming on top of the crystal. This technique holds promise for forming large areas of high quality single layer graphene on inexpensive substrates.

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